



JOURNAL OF

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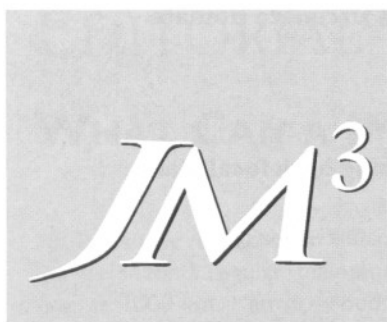
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About the Cover: *The figures are from the paper "Multilevel structures in deep proton lithography" by R. Kasztelanic.*

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